





Results from test 23

15th WP15 Meeting

Presenter

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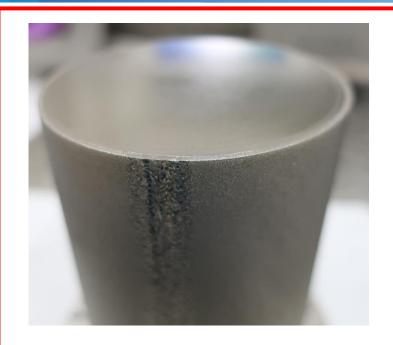
Early stage researcher

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TESTING SAMPLE







B-4.9		
Full HiPMS		
Chemical 'polishing' before coating		
Nb-AIN-NbN		
4um- <mark>8nm</mark> -180nm		

B-3.7

DCMS

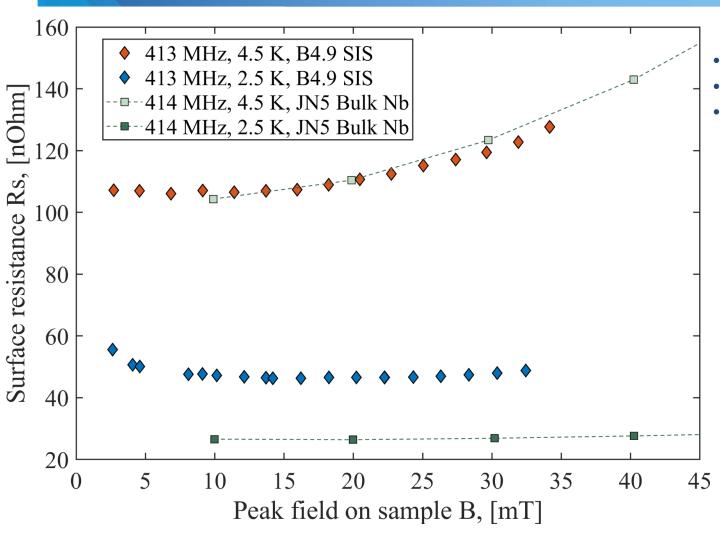
(BCP), exposed to air before SIS

Nb-AIN-NbN

4um-35nm-200nm

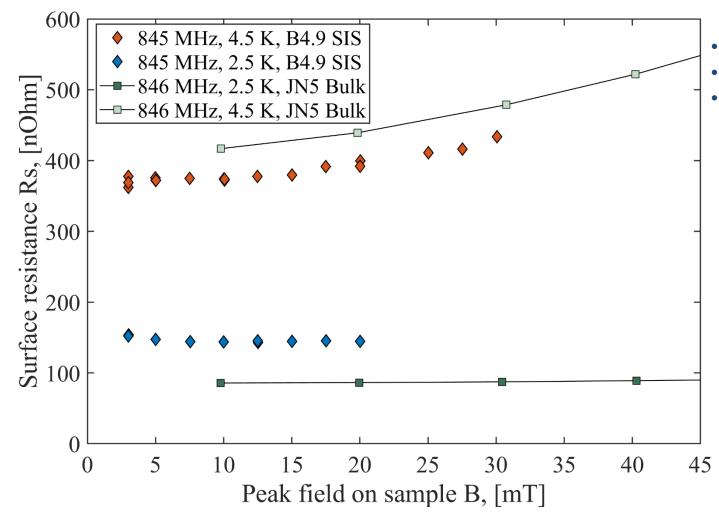






- Low Rres ~40 nOhm
- No non-monotonic
- Good Rs vs B quality

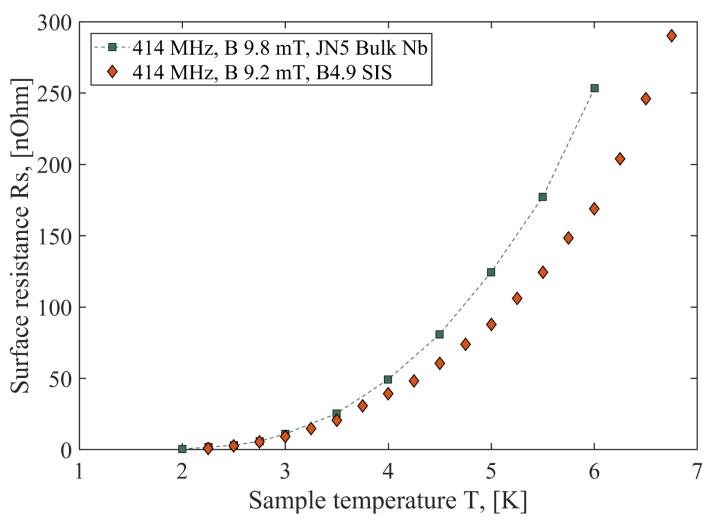




- Low Rres ~40 nOhm
- No non-monotonic
- Good Rs vs B quality

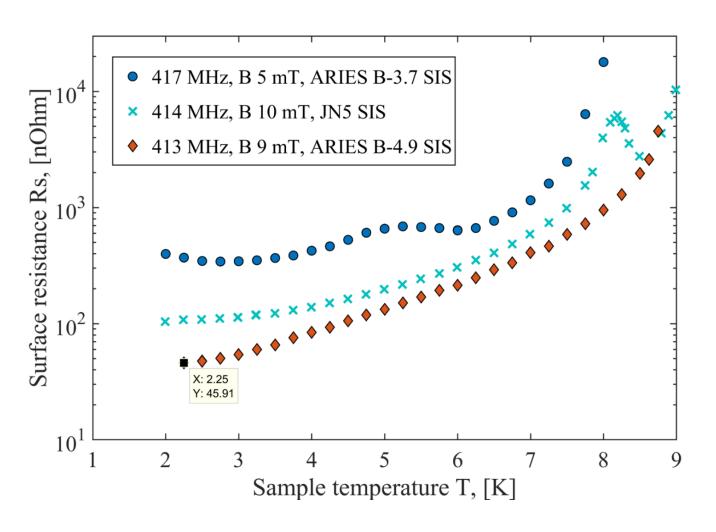
BCS PART





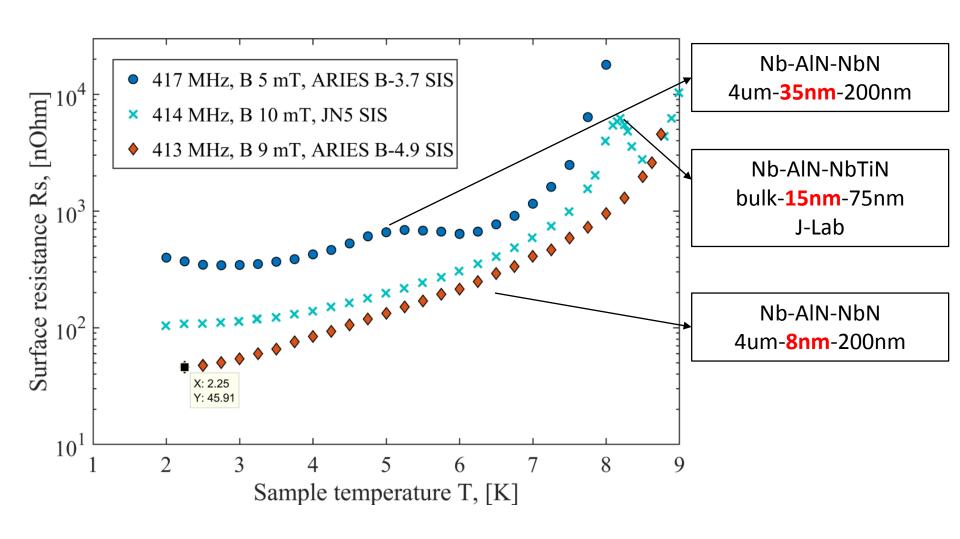
- Low Rres ~40 nOhm
- No non-monotonic
- Good Rs vs B quality
- BCS is lower





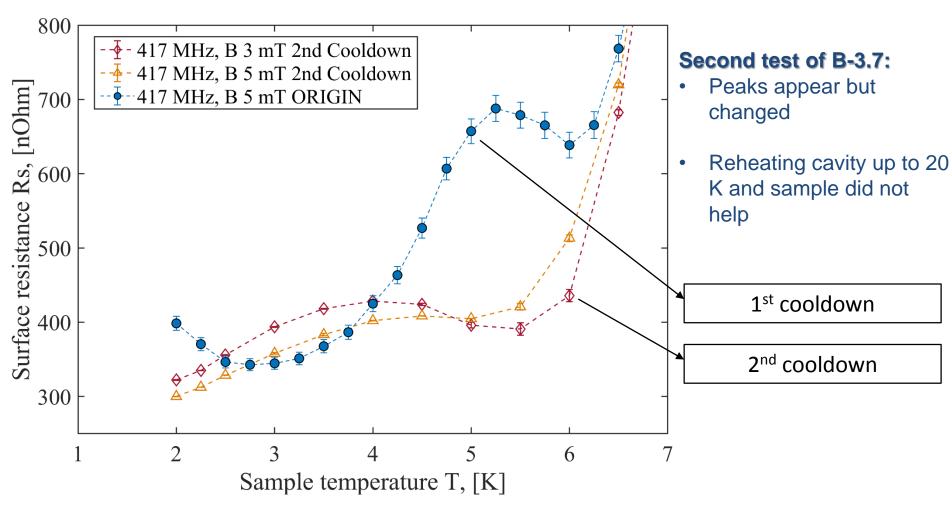






SECOND TEST OF 3.7

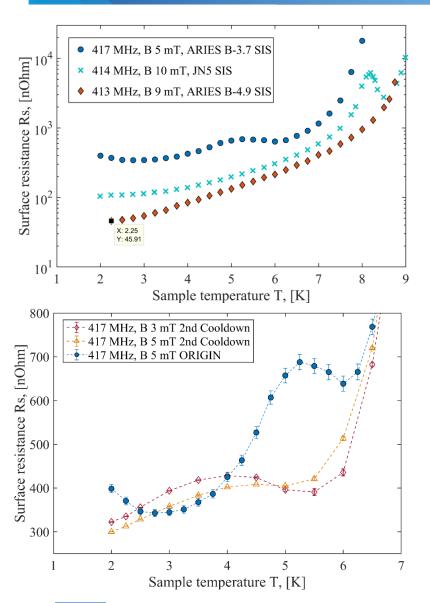






IDEAS AND EXPLANATIONS



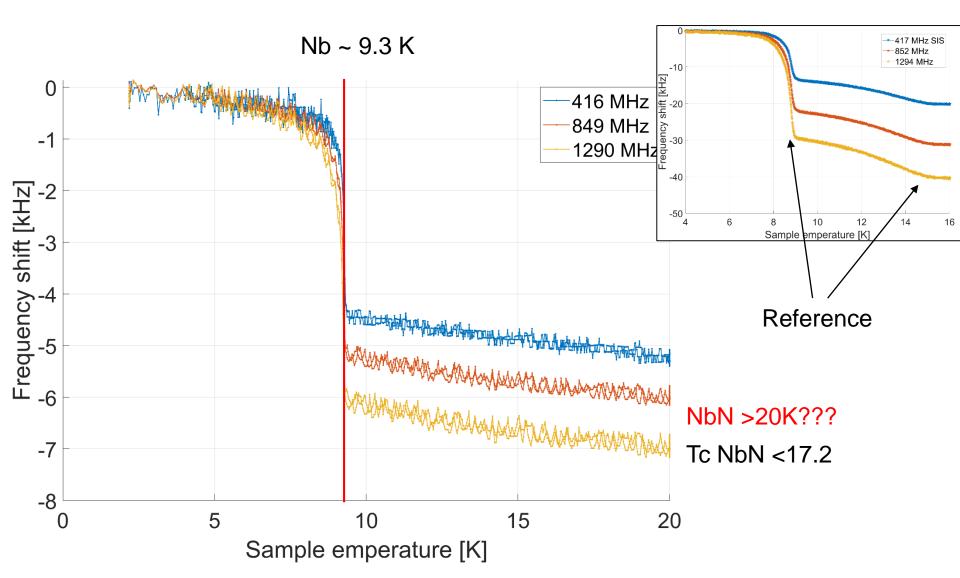


Ideas:

- Peaks appear due to thermal properties of the insulator layer
- Flux trapping effects?
- Effects bc. exposed to air?
- Effects of the sample edges quality?

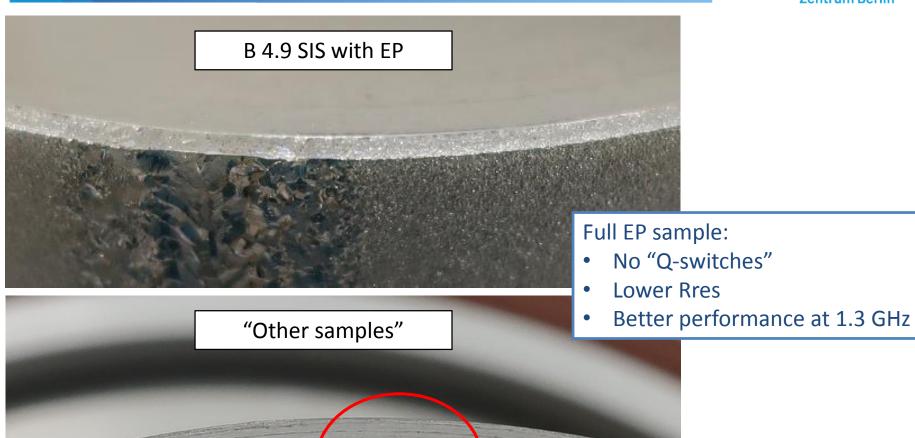






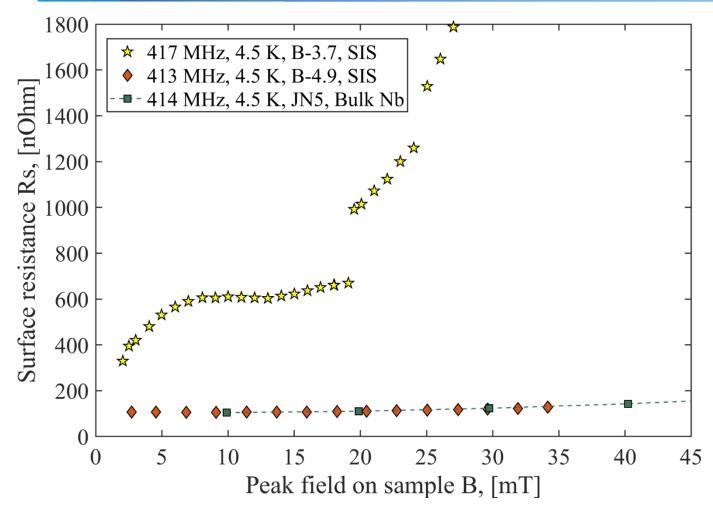








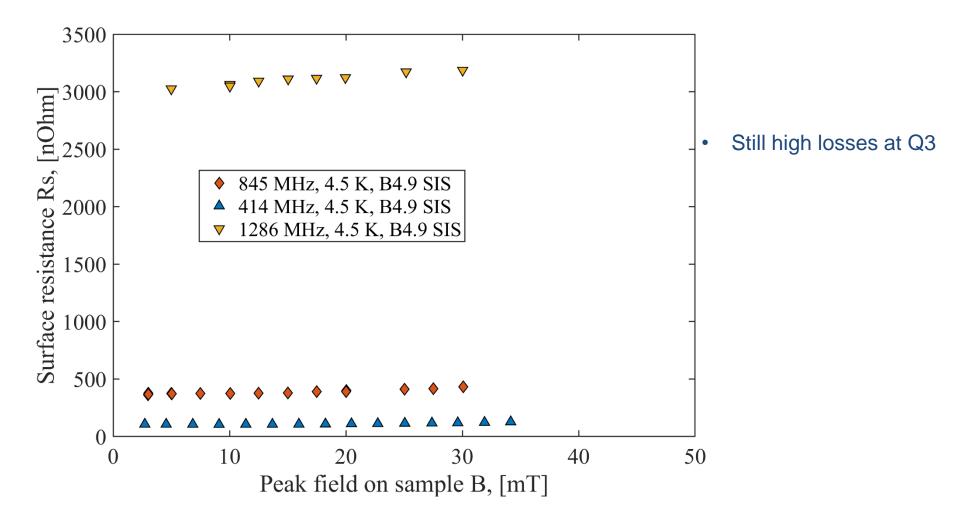




- Low Rres ~40 nOhm
- No non-monotonic
- Good Rs vs B quality









CONCLUSIONS?

- 1. Non-monotonic effect
- Effect of thickness, make the thickness 20-25 nm?
- No exposure to air after each layer is the reason?
- Flux trapping?

2. Chemical 'polishing' of the whole sample should be implemented in the procedure

	Rres	Mx field	Тс
400 MHz	~40 nOhm	~35 mT	??
800 MHz	~140 nOhm	~35 mT	??



CONCLUSIONS?

	Location, film	
B-2	CERN, Nb thick film	
B-3	HZB, SIS (siegen 35 nm)	
B-4	HZB, SIS (Siegen)	
B-5	RTU, Nb	



